BELLINGHAM, Washington, USA — Dong Gi Lee has been awarded the 2023 SPIE-BACUS Scholarship by SPIE, the international society for optics and photonics, and the BACUS Steering Committee, for potential contributions in the fields of microlithography, photomask technology and/or optical/EUV photolithography technologies.

Lee is pursuing a PhD in Material Science and Engineering under the guidance of Professor Jinho Ahn at Hanyang University (Republic of Korea). Lee is developing an EUV ptychography microscope for actinic mask inspection and investigating the effects of EUV pellicle defects on mask imaging performance via Through-pellicle mask imaging. Currently, he is focusing on the development of EUV phase shift mask evaluation technology using Fizeau interferometry, which enables the evaluation of the phase shift in EUV light passing through thin-film materials. As project leader, Lee is in the process of establishing international standards for EUV pellicle inspection apparatus.

Lee will be recognized in person at SPIE Photomask Technology + EUV Lithography in Monterey this October.

To view other 2023 scholarship press releases, please visit the 2023 Scholarship Winners page or learn more about SPIE scholarships on spie.org.

SPIE, the international society for optics and photonics, brings engineers, scientists, students, and business professionals together to advance light-based science and technology. The Society, founded in 1955, connects and engages with our global constituency through industry-leading conferences and exhibitions; publications of conference proceedings, books, and journals in the SPIE Digital Library; and career-building opportunities. Over the past five years, SPIE has contributed more than $22 million to the international optics community through our advocacy and support, including scholarships, educational resources, travel grants, endowed gifts, and public-policy development. www.spie.org.

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